Abstract

The purpose of the present invention is to provide a polishing pad that excels in level difference elimination performance and flattening performance. The polishing pad has a polishing layer comprising a polyurethane resin foam for which an isocyanate-terminated prepolymer and a curing agent are raw materials, and the polishing pad is characterized in that: the ratio of the content proportion of a crystalline phase and the content proportion of an amorphous phase in the polishing layer measured via a pulse NMR method in a wet state at 40 ˚C is 0.5-1.0; and the ratio of the content proportion of an intermediate phase and the content proportion of the amorphous phase in the polishing layer measured via a pulse NMR method in a wet state at 40 ˚C is 0.4-0.9.

[Fig.1]